## **Supplementary information**

Molecular topology-driven benzocyclobutene-based ultralow dielectrics with copper-matched low thermal expansion

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Fig.S1 The <sup>1</sup>H NMR of 4-acetylenyl benzocyclobutene.



Fig.S2 The <sup>1</sup>H NMR of 4-pinacyl borate benzocyclobutene.



Fig.S3 <sup>1</sup>H NMR (A), <sup>13</sup>C NMR (B) and MALDI-TOF (C) of Ph-BCB.



Fig.S4 <sup>1</sup>H NMR (A), <sup>13</sup>C NMR (B) and MALDI-TOF (C) of Ph-ene-BCB.



Fig.S5 <sup>1</sup>H NMR (A), <sup>13</sup>C NMR (B) and MALDI-TOF (C) of Ph-yne-BCB.



Fig.S6 <sup>1</sup>H NMR (A), <sup>13</sup>C NMR (B) and MALDI-TOF (C) of TPA-yne-BCB.



Fig.S7 <sup>1</sup>H NMR (A), <sup>13</sup>C NMR (B) and MALDI-TOF (C) of TPB-yne-BCB.



Fig.S8 The WAXS pattern of resins.





Fig.S10 Nanoindentation load-unload curves with displacement into surface of cured resins (a), Ph-BCB (b), Ph-ene-BCB (c), PH-yne-BCB (d), TPA-yne-BCB (e), and TPB-yne-BCB (f).